EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L21	809	((substrate wafer) and (reactor chamber) and (vapor and (reactant precursor))).CLM.	US-PGPUB	OR	ON	2006/07/18 14:41
L22	55905	(pulse cycle).CLM.	US-PGPUB	OR	ON	2006/07/18 14:41
L23	35446	(PSG (phosphosilicate and glass) (phosphorous and dop$3 (("Si" "O.sub.2"))) (silicon same (oxide dioxide))).CLM.	US-PGPUB	OR	ON	2006/07/18 14:46
L24	59	L21 and L22 and L23	US-PGPUB	OR	ON	2006/07/18 14:42
L26	30226	((plasma cvd ALD (atomic near5 layer near5 deposit$3) (chemical near5 vapor near5 deposit$3))).clm.	US-PGPUB	OR	ON	2006/07/18 14:44
L27	7511	23 and 26	US-PGPUB	OR	ON	2006/07/18 14:46
L28	317	27 and 21	US-PGPUB	OR	ON	2006/07/18 14:46
L29	75	("PO" near3 "OR").clm.	US-PGPUB	OR	ON	2006/07/18 14:47
L30	1	28 and 29	US-PGPUB	OR	ON	2006/07/18 14:47

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	809	((substrate wafer) and (reactor chamber) and (vapor and (reactant precursor))).CLM.	US-PGPUB	OR	ON	2006/07/18 14:29
L2	55905	(pulse cycle).CLM.	US-PGPUB	OR	ON	2006/07/18 14:29
L3	35446	(PSG (phosphosilicate and glass) (phosphorous and dop$3 (("Si" "O.sub.2"))) (silicon same (oxide dioxide))).CLM.	US-PGPUB	OR	ON	2006/07/18 14:29
L4	59641	((cvd chemisorb$3 (chemical same vapor same deposit$3) ALD (atomic same layer same deposit$3) pulse plasma)). CLM.	US-PGPUB	OR	ON	2006/07/18 14:29
L5	57	L4 and L1 and L2 and L3	US-PGPUB; USPAT; USOCR	OR	ON	2006/07/18 14:32
L6	2	(("20050009368") or ("20050112282")).PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/07/18 14:32
L7	1	6 and 5	US-PGPUB; USPAT; USOCR	OR	ON	2006/07/18 14:32
L8	15382	PSG (phosphours near5 doped near5 (silicon near5 (dioxide oxide)))	US-PGPUB; USPAT; USOCR	OR	ON	2006/07/18 14:35
L9	15382	PSG (phosphours near5 dop$3 near5 (silicon near5 (dioxide oxide)))	US-PGPUB; USPAT; USOCR	OR	ON	2006/07/18 14:35
L10	15382	L8 L9	US-PGPUB; USPAT; USOCR	OR	ON	2006/07/18 14:35
L11	490	L10 and (ALD (atomic near5 layer near5 deposit$3))	US-PGPUB; USPAT; USOCR	OR	ON	2006/07/18 14:35
L12	2	11 and ("PO" near3 "OR")	US-PGPUB; USPAT; USOCR	OR	ON	2006/07/18 14:38

L13	459	chemisorb$3	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/07/18 14:37
L14	155	L13 and (silicon (oxide dioxide))	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/07/18 14:37
L15	3	L14 and phosphorus	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/07/18 14:37
L16	0	14 and ("PO" near3 "OR")	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/07/18 14:39
L17	250227	(plasma cvd ALD (atomic near5 layer near5 deposit$3) (chemical near5 vapor near5 deposit$3))	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/07/18 14:38
L18	2098	L17 and (BPSG PSG (borophosphosilicate near5 glass) (dop$3 near5 silicon near5 (oxide dioxide)))	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/07/18 14:38
L19	38	L18 and (phosphorus near5 dop$3 near5 silicon near5 (oxide dioxide))	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/07/18 14:39
L20	0	19 and ("PO" near3 "OR")	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/07/18 14:39